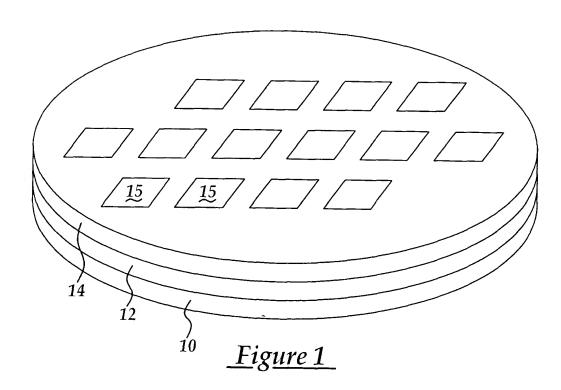
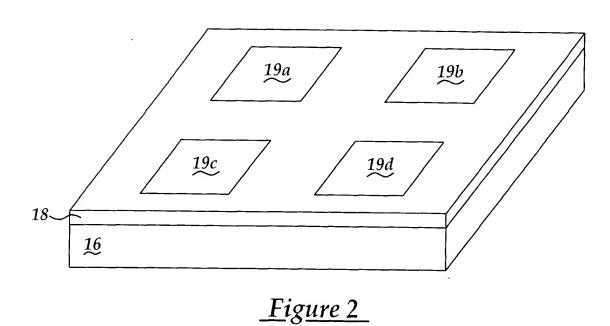
Inventor: Shin-Rung Lu

Serial No.: To Be Assigned Filed: Herewith

For: Multiple Exposure Method for Forming Patterned Photoresist Layer

Attorney Doc. No.: 67,200-1145





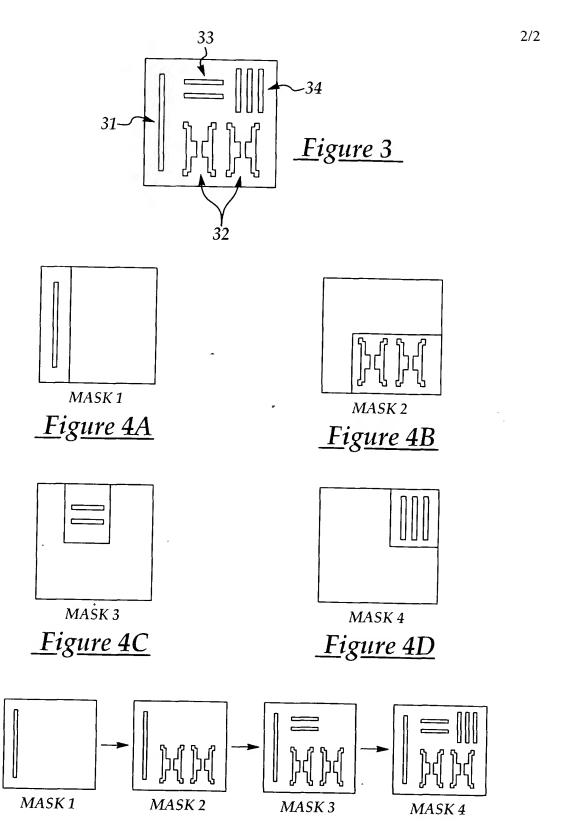
1/2

Inventor: Shin-Rung Lu

Serial No.: To Be Assigned Filed: Herewith

For: Multiple Exposure Method for Forming Patterned Photoresist Layer

Attorney Doc. No.: 67,200-1145



<u>Figure 5</u>